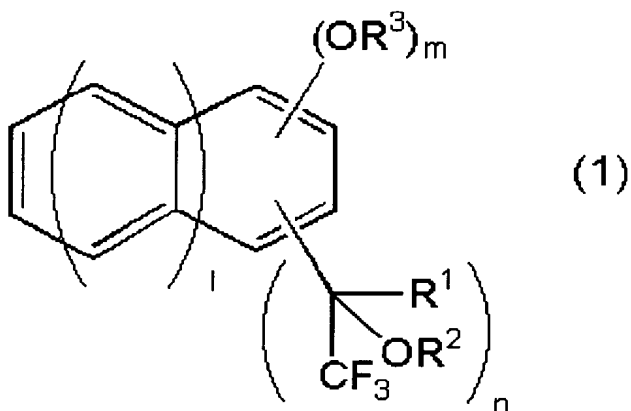


**Amendments to the Specification:**

Please replace the paragraph beginning at page 2, line 16 with the following amended paragraph:

According to the present invention, there is provided a fluorine-containing compound represented by the formula 1,



where  $R^1$  is a methyl group or trifluoromethyl group,

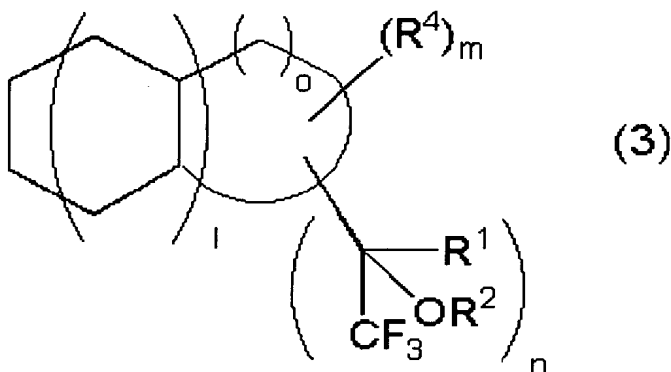
each of  $R^2$  and  $R^3$  is independently a hydrogen atom or a group containing (a) a hydrocarbon group having a straight-chain, branched or ring form and having a carbon atom number of 1-25 or (b) an aromatic hydrocarbon group, each of the hydrocarbon group and the aromatic hydrocarbon group independently optionally containing at least one of a fluorine atom, an oxygen atom and a carbonyl bond,

$l$  is an integer of from 0 to 2, each of  $m$  and  $n$  is independently an integer of 1-5 to satisfy an expression of  $m+n \leq 6$ , and

when at least one of  $R^1$ ,  $R^2$  and  $R^3$  is in a plural number, the at least one of  $R^1$ ,  $R^2$  and  $R^3$  may be identical with or different from each other.

Please replace the paragraph beginning at page 3, line 16 with the following amended paragraph:

According to the present invention, there is provided a fluorine-containing compound represented by the formula 3,



where  $R^1$  and  $R^2$  are defined as in the formula 1,

$R^4$  is independently a hydrogen atom or a group containing (a) a hydrocarbon group having a straight-chain, branched or ring form and having a carbon atom number of 1-25 or (b) an aromatic hydrocarbon group, each of the hydrocarbon group and the aromatic hydrocarbon group independently optionally containing at least one of a fluorine atom, an oxygen atom and a carbonyl bond,

$l$  is an integer of from 0 to 2, each of  $m$  and  $n$  is independently an integer of 1-9 and  $o$  is an integer of 1-8 to satisfy an expression of  $m+n \leq o+2$ , and

when at least one of  $R^1$ ,  $R^2$  and  $R^4$  is in a plural number, the at least one of  $R^1$ ,  $R^2$  and  $R^4$  may be identical with or different from each other.

Please replace the paragraph beginning at page 18, line 4 with the following amended paragraph:

The above-mentioned acid generator for a resist composition is not particularly limited. It can be suitably selected from acid generators for

chemically amplified resists. Examples of such acid generators are bisulfonyldiazomethanes, nitrobenzyl derivatives, onium salts, halogen-containing triazine compounds, cyano group-containing oximesulfonate compounds, and other oximesulfonate compounds. The acid generator may be used in the form of a single compound or a mixture of at least two compounds. The content of the acid generator in the resist composition may be 0.5-20 parts by weight, relative to 100 parts by weight of the polymer. If it is less than 0.5 parts by weight, the resist composition may become insufficient in image forming capability. If it is greater than 20 parts by weight, it may become difficult to prepare a uniform solution of the resist composition. Thus, the resulting solution may become inferior in storage stability